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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Atty. Docket No. (Opt.) UBAT1510



Applicant Gregory R. Hanson et al.	
Application Number 10/649,251	Filed August 26, 2003
For Spatial Heterodyne Interferometry for Transmission (SHIFT) Measurements	
Group Art Unit 2631	Examiner Unknown

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Certificate of Mailing Under 37 C.F.R. 1.8
I hereby certify that this correspondence is being deposited with the U.S. Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on <u>June 14</u> , 2004.
 Laura M. McGuire

Applicants respectfully request, pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, that the art listed on the attached PTO-1449 form be considered and cited in the examination of the above-identified application. A copy of the art is enclosed for the convenience of the Examiner. Furthermore, pursuant to 37 C.F.R. §§ 1.97(g) and (h), no representation is made that a search has been made or that this art is material to patentability of the present application.

While Applicants believe no fees are due, if any fees are due, the Commissioner is hereby authorized to charge Deposit Account No. 50-0456 of Gray Cary Ware & Freidenrich LLP.

Applicants respectfully submit that the claims of Applicants' above-referenced patent application are patentably distinguishable from these references.

Respectfully submitted,

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/649,251		
		Filing Date	August 26, 2003		
		First Named Inventor	Gregory R. Hanson		
		Group Art Unit	2621		
		Examiner Name	Unknown		
Sheet	1	of	1	Attorney Docket Number	2500940-991510 (UBAT1510)
NON-PATENT LITERATURE DOCUMENTS					
	C1	Edgar Volkl, "Introduction to Electron Holography", pp. 133-138, published by Kluwer Academic/Plenum Publishers, New York, 1999.			
	C2	Jacob et al., "High Resolution Photomask Transmission and Phase Measurement Tool", Metrology, Inspection and Process Control for Microlithography XVI, Proceedings of SPIE Vol. 4689, pp. 70-82, 2002.			
	C3	Thomas et al., "Direct to Digital Holography for Semiconductor Wafer Defect Detection and Review", Design, Process Integration, and Characterization for Microelectronics, Proceedings of SPIE Vol. 4692, pp. 180-194, 2002.			
	C4	"Phase Contrast Microscopy" Authors unknown, date unknown			
Examiner Signature				Date Considered	